

Z4MS™ Tetramethylsilane

Product Description

Dow Corning® Z4MS™ CVD Precursor is a liquid used for the chemical vapor deposition of high quality low dielectric constant films.

Air Products: Global Supplier of CVD Low-k Dielectric Precursors

Air Products offers a comprehensive low-k package, including a variety of high-purity electronic specialty gases, its Schumacher unit's low-k chemical product line, delivery equipment and MEGASYS® on-site management services to maximize productivity and speed the development of new systems.

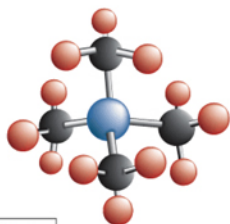
The company's portfolio of interlayer dielectric (ILD) precursor products includes SiH₄, 1MS, SiF₄ and chlorosilanes (TCS, STC, DCS). Air Products' Schumacher unit offers several proven ILD products, including TEOS, ZTOMCATS™, 3MS™ and DMDMOS CVD low-k precursors, and our MesoELK™ SiO₂ precursor.

In addition, Air Products offers a full line of gas and chemical delivery equipment providing a high degree of safety and effective use of its low-k products. Offerings include the company's CHEMGUARD® and GASGUARD® gas cabinets.

Table 1

Physical Characteristics

Formula	Si(CH ₃) ₄
Molecular Weight	88.2
Boiling Point	26.6° C
Freezing Point	-99° C
Flash Point	-27° C
Specific Gravity	0.648 (H ₂ O=1)
Vapor Density	602 Torr



*Tetramethylsilane (Z4MS)
molecule*



For More Information

This datasheet has provided only a brief overview of Air Products' wide range of low-k solutions. If you would like more information, please contact:

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